The drawings are objected to by the Examiner. Specifically, the Examiner alleged that Figs. 8A-8H, 8A'-8H' and 9A-9C should be designated as "Prior Art".

Applicant submits herewith a Request for Approval of Drawing Changes to designate Figs. 8A-8H, 8A'-8H' and 9A-9C as "Prior Art". Accordingly, this objection should be withdrawn.

Claims 1-4 stand rejected under 35 U.S.C. § 102(b) as being allegedly anticipated by U.S. Patent No. 5,992,974 (Miyata). Claims 5 and 6 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over Miyata. The grounds of rejection are respectfully traversed.

The present invention is directed to a method for manufacturing a liquid jet recording head. In this method, the top plate is anisotropically etched through a mask layer and the liquid chamber is formed to have a substantially rectangular shape at the nozzle surface of the top plate by over-etching portions of the compensation patterns.

Miyata is directed to an ink-jet head having nozzle openings through which ink droplets are discharged. The Examiner has alleged that this reference teaches overetching portions with the compensation pattern at column 7, line 65, through column 8, line 6. Applicant respectfully disagrees.

Miyata merely states that "channels can be formed by anisotropically etching a single silicon monocrystalline substrate". This is clearly not a disclosure or a teaching of over-etching portions with the compensation patterns so that the liquid chamber is formed to have a substantially rectangular shape at the nozzle surface of the top plate, as defined by the present invention and recited in claim 1. Accordingly, the present invention is clearly patentable over Miyata.

Wherefore, Applicant respectfully requests that the above objection and rejections be withdrawn and the present application be passed to issue.

Applicant's undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

Strorney for Applicant

Registration No. 49,5/2

FITZPATRICK, CELLA, HARPER & SCINTO 30 Rockefeller Plaza New York, New York 10112-3801

Facsimile: (212) 218-2200

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